

Radiation Hardened Dual JK Flip Flop

Intersil's Satellite Applications Flow™ (SAF) devices are fully tested and guaranteed to 100kRAD total dose. These QML Class T devices are processed to a standard flow intended to meet the cost and shorter lead-time needs of large volume satellite manufacturers, while maintaining a high level of reliability.

The Intersil HCTS109T is a Radiation Hardened Dual JK Flip Flop with set and reset. The flip flop changes state with the positive transition of the clock (CP1 or CP2).

Specifications

Specifications for Rad Hard QML devices are controlled by the Defense Supply Center in Columbus (DSCC). The SMD numbers listed below must be used when ordering.

Detailed Electrical Specifications for the HCTS109T are contained in SMD 5962-95769. A "hot-link" is provided from our website for downloading.

www.intersil.com/spacedefense/newsafclasst.asp

Intersil's Quality Management Plan (QM Plan), listing all Class T screening operations, is also available on our website.

www.intersil.com/quality/manuals.asp

Ordering Information

ORDERING NUMBER	PART NUMBER	TEMP. RANGE (°C)
5962R9576901TEC	HCTS109DTR	-55 to 125
5962R9576901TXC	HCTS109KTR	-55 to 125

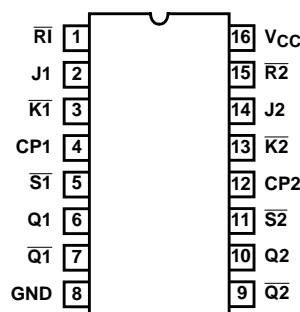
NOTE: **Minimum order quantity for -T is 150 units through distribution, or 450 units direct.**

Features

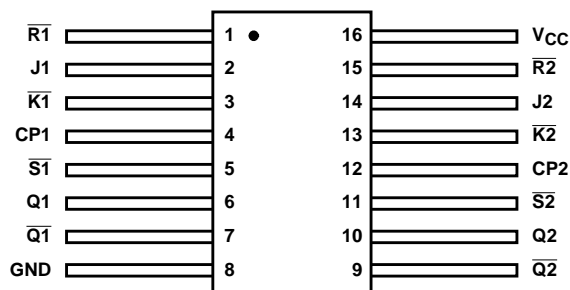
- QML Class T, Per MIL-PRF-38535
- Radiation Performance
 - Gamma Dose (γ) 1×10^5 RAD(Si)
 - Latch-Up Free Under Any Conditions
 - SEP Effective LET No Upsets: >100 MEV-cm²/mg
 - Single Event Upset (SEU) Immunity $< 2 \times 10^{-9}$ Errors/Bit-Day (Typ)
- 3 Micron Radiation Hardened SOS CMOS
- Significant Power Reduction Compared to LSTTL ICs
- DC Operating Voltage Range: 4.5V to 5.5V
- LSTTL Input Logic Compatibility
 - $V_{IL} = 0.8V$ Max
 - $V_{IH} = V_{CC}/2$ Min
- Input Current Levels $I_i \leq 5mA$ at V_{OL}, V_{OH}

Pinouts

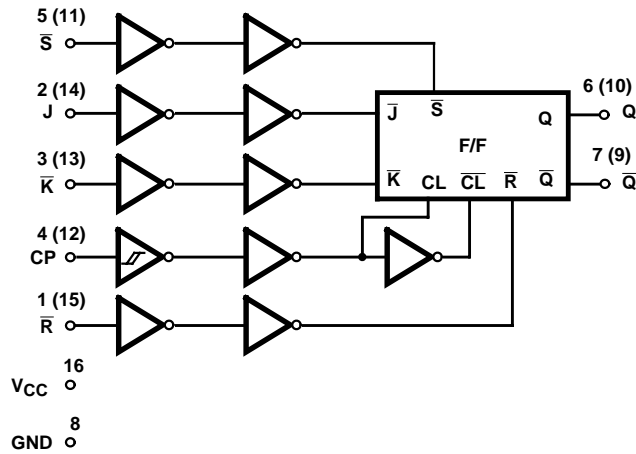
HCTS109T (SBDIP), CDIP2-T16
TOP VIEW



HCTS109T (FLATPACK), CDFP4-F16
TOP VIEW



Functional Diagram



TRUTH TABLE

INPUTS					OUTPUTS	
\bar{S}	\bar{R}	CP	J	\bar{K}	Q	\bar{Q}
L	H	X	X	X	H	L
H	L	X	X	X	L	H
L	L	X	X	X	H†	H†
H	H		L	L	L	H
H	H		H	L	Toggle	
H	H		L	H	No Change	
H	H		H	H	H	L
H	H	L	X	X	No Change	

† Unpredictable and unstable condition if both \bar{S} and \bar{R} go high simultaneously.

Die Characteristics

DIE DIMENSIONS:

2261 μ m x 2235 μ m x 533 μ m \pm 51 μ m)
 89 x 88 x 21mils \pm 2mil

METALLIZATION:

Type: Al Si
 Thickness: 11k \AA 1k \AA

SUBSTRATE POTENTIAL:

Unbiased Silicon on Sapphire

BACKSIDE FINISH:

Sapphire

PASSIVATION:

Type: Silox (SiO₂)
 Thickness: 13k \AA \pm 2.6k \AA

WORST CASE CURRENT DENSITY:

< 2.0e5 A/cm²

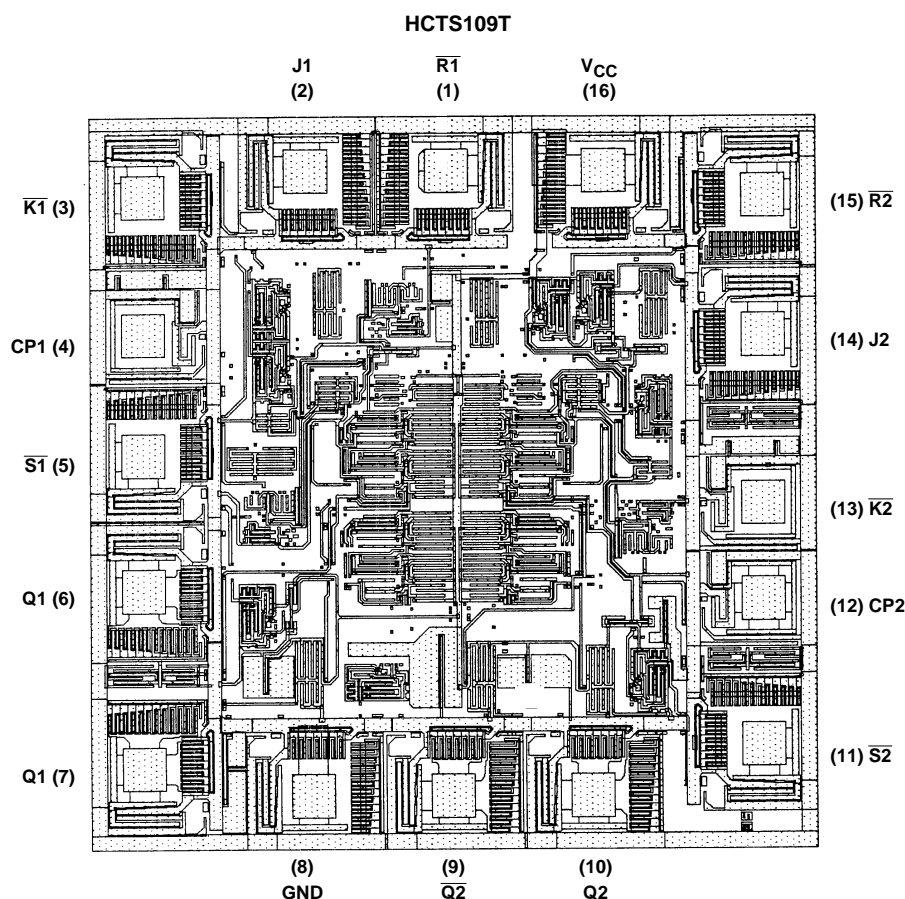
TRANSISTOR COUNT:

268

PROCESS:

CMOS SOS

Metalization Mask Layout



NOTE: The die diagram is a generic plot form a similar HCS device. It is intended to indicate approximate die size and bond pad location. The mask series for the HCTS109 is TA14440A.

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